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### Dynamics of voltage-driven oscillating insulator-metal transitions

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Recent experiments demonstrated emerging alternating insulator and metal phases in Mott insulators actuated by a direct bias voltage, leading to oscillating voltage outputs with characteristic frequencies. Here we develop a physics-based nonequilibrium model to describe the dynamics of oscillating insulator-metal phase transitions and experimentally validate it using a VO<sub>2</sub> device as a prototype. The oscillation frequency is shown to scale monotonically with the bias voltage and series resistance and terminate abruptly at lower and upper device-dependent limits, which are dictated by the nonequilibrium carrier dynamics. We derive an approximate analytical expression for the dependence of the frequency on the device operating parameters, which yields a fundamental limit to the frequency and may be utilized to provide guidance to potential applications of insulator-metal transition materials as building blocks of brain-inspired non-Von Neumann computers.

#### I. INTRODUCTION

Insulator-metal transitions (IMTs) belong to a large class of phase transitions involving dramatic changes in electronic structures, which are often accompanied by lattice deformations. The vanadium dioxide  $(VO_2)$ , a strongly correlated system, is perhaps the best studied material that exhibits an IMT [1-4]. Due to the fact that its IMT is near room temperature,  $VO_2$  has been explored for many potential applications such as memristors, sensors, and Mott field-effect transistors [5–9]. Experiments employing a two-terminal  $VO_2$  device with a resistor in series under a direct voltage demonstrated the possible emergence of voltage oscillation across the  $VO_2$  channel resulted from automatic alternation of the insulator and metal phases [10-20]. Such electronic oscillators can emulate neural behavior found in animal brains [21], and the coupling between oscillators leads to synchronization of charge oscillations which can potentially be utilized for non-Boolean computing [22].

There have been a number of theoretical models proposed to describe the voltage oscillation dynamics in VO<sub>2</sub> [23–25]. However, all existing models were based on the assumption that the oscillating phase is kinetically in a quasi-steady state in its instantaneous response to temperature and/or voltage stimuli. The voltage oscillations in these quasi-steady models are purely charging and discharging cycles of a capacitor with their frequencies and oscillation windows defined phenomenologically by the measured switching voltages and on/off resistances. On the other hand, experiments on the voltage-induced IMT in VO<sub>2</sub> revealed that the switching voltages are thermally set by Joule heating [26, 27], but a quasi-steady model incorporating the thermally triggered IMT cannot produce voltage oscillations [23] nonetheless.

Here we report a physics-based nonequilibrium model to describe the dynamics of the IMT and the corresponding voltage oscillation beyond the quasi-steady assumption. In particular, It explicitly incorporates the nonequilibrium dynamics of free charge carriers with a lifetime on the order of 10  $\mu$ s [28, 29], comparable to periods of possible voltage oscillations. This is important since the free carriers not only determine the device resistance, but also can drive an IMT when their concentration is beyond a critical value [30]. The model yields the correct voltage oscillation characteristics validated by our experiments and still exhibits thermally determined switching voltages as observed in experiments. Importantly, we show that the nonequilibrium carrier dynamics imposes a fundamental limit to the maximal oscillation frequency and identify the physical properties of Mott insulators that will further enhance the maximal frequency. The analysis based on this model and the comparison with experimental measurements clearly demonstrate the key role of the nonequilibrium dynamics of free charge carriers in actuating the voltage oscillation in  $VO_2$ .

#### II. PHYSICS-BASED NONEQUILIBRIUM MODEL

To focus on the dynamics of the oscillating IMT rather than the two-phase morphological patterns, we assume the VO<sub>2</sub> channel of the device to be both homogeneous and charge-neutral during the entire IMT process. We describe the thermodynamic state of VO<sub>2</sub> during the IMT using an electron-correlation order parameter  $\xi$  as well as a structural order parameter  $\eta$  with  $\xi = 0$  and  $\eta = 0$  representing the metallic rutile (R) phase and  $\xi \sim -1$  and  $\eta \sim 1$  the insulating monoclinic (M1) phase [31–34]. The order parameters evolve to minimize

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the total free energy of the system, and for a homogeneous and charge-neutral system, the total free energy density  $f(T; \xi, \eta, n)$ , where T is the temperature and n is the free electron density. We note that f is referencing to that of the metallic R phase. The free energy density fcontains two contributions: the intrinsic bulk free energy density  $f_b(T;\xi,\eta)$  and the free energy density of excess free charge carriers  $f_{eh}(T;\xi,n)$ , i.e.,  $f = f_b + f_{eh}$  [33, 35– 37]. The intrinsic bulk free energy density  $f_b$  is approximated by a Landau polynomial with respect to the order parameters [31]. Since the time constants of the relaxation of the order parameters are on the order of picoseconds or less [30, 38] far shorter than the typical voltage oscillation periods in VO<sub>2</sub> oscillators ( $\gtrsim 1 \ \mu s$ ), we assume that the order parameters describing the IMT establish equilibrium instantaneously for a given temperature and carrier concentration (considering the temperature and carrier concentration to be independent natural variables), i.e.,

$$\frac{\partial f}{\partial \xi} = \frac{\partial f_b}{\partial \xi} + 2\gamma \xi [n - n_i(T;\xi)] \approx 0, \qquad (1)$$

$$\frac{\partial f}{\partial n} = \frac{\partial f_b}{\partial \eta} \approx 0,\tag{2}$$

where we have used the relation  $\partial f_{eh}/\partial \xi = 2\gamma \xi (n - \xi)$  $n_i$  [33].  $n_i \approx \sqrt{N_c N_v} \exp(-\gamma \xi^2 / 2k_B T)$  is the intrinsic free carrier density, where  $k_B$  is the Boltzmann constant and  $N_c$  and  $N_v$  are the effective densities of states of the conduction and the valence bands, respectively [33]. Here the energy gap  $E_q$  naturally depends on the electronic order parameter and is approximated by  $E_g\approx\gamma\xi^2$ where  $\gamma$  is the energy gap of the M1 phase [31–33]. Similar to the thermal driving force  $(\partial f_b/\partial \xi, \partial f_b/\partial \eta)$ , the term  $2\gamma\xi(n-n_i)$  in Eq. (1) is the *electronic* driving force that can reduce the electron correlation  $(\xi)$  and induce phase change. This term distinguishes the current model from the existing quasi-steady models [23–25]. Due to this term, for a given temperature [n is subsequently determined by its equation of evolution Eq. (3)],  $\xi$  will not be at equilibrium since the resulted n will not necessarily be at equilibrium.

Existing experiments showed that the lifetime of the minority carriers in heavily doped VO<sub>2</sub>,  $\tau$ , is around 10  $\mu$ s [28, 29], comparable to the typical oscillation periods. We use this value to approximate the VO<sub>2</sub> intrinsic carrier lifetime because to our knowledge there is no other reported measurement of the intrinsic carrier lifetime in the literature. Therefore, it is critical to explicitly incorporate the carrier dynamics in a theoretical model for voltage oscillation. Here we describe the dynamics of free electrons using

$$\frac{\mathrm{d}n}{\mathrm{d}t} = K(n_i^2 - n^2),\tag{3}$$

where  $K = 1/2n_r\tau$  is the recombination rate and  $n_r$  is a reference electron density.

The temperature evolution in  $VO_2$  subject to a voltage drop V is simply described by the heat equation with a



FIG. 1. (a) Schematics of the VO<sub>2</sub> oscillator.  $V_a$  is the bias direct voltage,  $R_s$  is the series resistor,  $V_s$  denotes the voltage drop across the series resistor, and C represents the parasitic capacitance explicitly or it could be an external capacitor. (b) Oscillation patterns of  $V_s/V_a$ , the VO<sub>2</sub> resistance R, the order parameters, and the temperature T at  $V_a = 7.8$  V and  $R_s = 4.7$  k $\Omega$ . The light-blue and the light-red shaded regions indicate the processes of the MIT and the IMT, respectively. The numbered red crosses correspond to the phases in Fig. 2(a).

heat source arising from Joule heating,

$$C_v \frac{\mathrm{d}T}{\mathrm{d}t} + \frac{\mathrm{d}u}{\mathrm{d}t} = \frac{V^2}{RL_x L_y L_z} - \frac{h(T - T_s)}{L_z},\qquad(4)$$

where  $C_v$  is the heat capacity per unit volume of the metallic R phase,  $T_s$  is the ambient temperature, h is the convective heat dissipation coefficient, and u is the internal energy density arising from f. The internal energy density of the metallic R phase can be approximated by  $C_v T$ , so  $C_v T + u$  constitutes the total internal energy density of  $VO_2$  (f and u are referencing to those of the metallic R phase, respectively).  $L_x$ ,  $L_y$  and  $L_z$  are the width, length (in the direction of the electric field), and thickness of the  $VO_2$  channel of a device, respectively.  $R = L_u/L_x L_z e \mu n$  is the resistance of the VO<sub>2</sub> channel, where e is the elementary charge and  $\mu$  is the carrier mobility. Note that R depends on the real-time nonequilibrium density of free electrons n, not the equilibrium density  $n_i$ . The du/dt term takes into account the latent heat effect of the first-order IMT [35].

We consider a VO<sub>2</sub> oscillator device schematically depicted in Fig. 1(a). A VO<sub>2</sub> two-terminal device is connected to a direct voltage source  $V_a$  through a series resistor  $R_s$ . C denotes the parasitic capacitance of the



FIG. 2. (a) Phases at a sequence of moments represented by the order parameters superimposed on the intrinsic bulk free energy density landscape for  $V_a = 7.8$  V and  $R_s = 4.7$  k $\Omega$ . The red crosses in (a) correspond to those in Fig. 1(b). The temperature at each moment is shown. The M1 and R minima are marked in  $\oplus$  and  $\oplus$ , respectively. (b) *I-V* characteristics of VO<sub>2</sub> at  $V_a = 7.8$  V and  $R_s = 4.7$  k $\Omega$ . The *x* coordinate is the voltage drop across the VO<sub>2</sub> channel.  $I_1$  and  $I_2$  are the current through VO<sub>2</sub> (including the capacitor current) and the current through the resistor (excluding the capacitor current), respectively.

circuit, or an external capacitor that could be added to the circuit. The voltage drop across the series resistor  $V_s$ satisfies the Kirchhoff's law,  $V = V_a - V_s$  and

$$V_s + R\left(C\frac{\mathrm{d}V_s}{\mathrm{d}t} + \frac{V_s}{R_s}\right) = V_a.$$
(5)

If steady states are assumed, the electronic driving force is zero and thus the switching voltage is solely determined by the Joule heating effect, consistent with experiments [26, 27].

Before moving to the simulation results, we analyze some qualitative behaviors that can be predicted by the nonequilibrium model. We expect that the VO<sub>2</sub> resistance, which directly depends on the free electron density n, will not strictly follow the quasi-steady resistance determined by the VO<sub>2</sub> temperature. This is clear from Eq. (3), which indicates that n will lag behind  $n_i$ . The time constant for the temperature evolution  $C_v L_z/h$  will be far shorter than the voltage oscillation periods for thin films (small  $L_z$  and large h). In this case, Eq. (4) corresponds to quasi-steady states and the voltage oscillation period is determined by the free electron lifetime and the RC time constant. The oscillation period will be longer for longer free electron lifetimes and larger  $R_sC$  values.

#### III. NONEQUILIBRIUM CHARACTERISTICS OF OSCILLATING IMTS

In our experiments, the two-terminal device in Fig. 1(a) employs a VO<sub>2</sub> thin film grown on a sapphire substrate, and is supplied with a direct voltage with a resistor in series [35]. The parameters used for modeling the device characteristics by simultaneously solving Eqs. (1-5) are the same as those in experiments [35]. Fig-

ure 1(b) shows the calculated oscillation patterns of various variables at  $V_a = 7.8$  V and  $R_s = 4.7$  k $\Omega$ . The processes of the metal-insulator transition (MIT, marked as light blue) and the IMT (marked as light red) are identified by falling and rising parts of the  $\xi$  pattern, respectively. The voltage drop across the series resistor has an oscillation amplitude around 18% of the bias voltage. It rises quickly and falls relatively slowly with a ratio of the rise and fall times of 0.26 and transits from rise to fall smoothly, consistent with experiments [10, 11, 22].  $|\xi|$  and  $|\eta|$  never reach exactly 0 and 1, indicating that  $VO_2$  is never in the fully metallic or fully insulating state. The peaks of  $\xi$  and the troughs of R have a delay of 0.19  $\mu$ s to the peaks of temperature, meaning that the  $VO_2$  channel at the highest temperature is actually not the most metallic, which is a clear evidence of the noninstantaneous response of the electronic phase to temperature. The temperature reaches 450 K consistent with the experiment [16]. The peaks of  $\xi$  also have a short delay to the troughs of  $\eta$ . Furthermore, the peaks of R have a delay of 0.19  $\mu$ s to the troughs of  $\xi$ , revealing that the  $VO_2$  resistance has a finite response time to the electronic phase.

Next we examine the evolution of the phase and the free energy landscape during the oscillation [Fig. 2(a)]. From a trough of the  $\xi$  pattern to its trailing peak [red crosses in Fig. 1(b)], the phase evolves from the vicinity of the M1 minimum of  $f_b$  to the vicinity of the saddle point. From the peak to the next trough, the phase returns to the vicinity of the M1 minimum yet following a different route from the pathway on which it appears. The phase never resides exactly at the minimum or the saddle point of  $f_b$ , indicating that during the oscillation the state is always transient. The non-steady phase trajectory corresponds to non-steady flows in the *I-V* plane as shown in Fig. 2(b). Both the current through VO<sub>2</sub> ( $I_1$ ) and



FIG. 3. (a) Experimentally measured (markers) and simulated (lines) frequency scaling with the bias voltage  $V_a$  at  $R_s = 4.7 \text{ k}\Omega$ and 10 k $\Omega$ . The scaling calculated with different  $\tau$  and C is shown. I:  $R_s = 4.7 \text{ k}\Omega$ ,  $\tau = 7 \mu \text{s}$ , C = 250 pF; II:  $R_s = 10 \text{ k}\Omega$ ,  $\tau = 7 \mu \text{s}$ , C = 250 pF; III:  $R_s = 4.7 \text{ k}\Omega$ ,  $\tau = 11 \mu \text{s}$ , C = 550 pF; IV:  $R_s = 10 \text{ k}\Omega$ ,  $\tau = 11 \mu \text{s}$ , C = 550 pF; V:  $R_s = 4.7 \text{ k}\Omega$ ,  $\tau = 14 \mu \text{s}$ , C = 700 pF; VI:  $R_s = 10 \text{ k}\Omega$ ,  $\tau = 14 \mu \text{s}$ , C = 700 pF. (b) Experimentally measured (markers) and analytical (lines) frequency scaling with  $R_s$  at different  $V_a$ . (c) Numerically simulated (solid lines) and analytical (dotted lines) frequency scaling with  $V_a$  at various  $R_s$ . The colored numbers indicate the corresponding  $R_s$  values in units of kiloohm. The light yellow and light blue shades mark the regions of oscillation and no oscillation, respectively. (d) Numerically simulated (solid lines) boundaries of the range of oscillation superimposed on the frequency map over the bias voltage and series resistance obtained by the analytical formulae.

the current through the series resistor  $(I_2)$  possess the negative differential resistance (NDR) with non-steady intermediate NDR states. In contrast, a quasi-steady model [23–25] is not possible to access the non-steady intermediate states that connect the fully metallic and fully insulating states.

We then study the oscillation frequency scaling with the bias voltage and series resistance. The calculations show that the frequency increases monotonically as the voltage increases [Fig. 3(a)]. As  $V_a$  increases, the oscillation suddenly emerges at a finite low bias and then gets overdamped at a high bias, which mark the low and high bias limits on the calculated frequency scaling curves. Indeed,  $VO_2$  remains in the M1 phase for sufficiently low voltages and is excited permanently to the R phase for sufficiently high voltages. These are all consistent with our experimental results. The simulations also reveal that larger  $\tau$  and C reduce the slopes of the frequency scaling curves and shift the curves to lower bias. For  $\tau = 14 \ \mu \text{s}$  and  $C = 700 \ \text{pF}$  [35], the calculated frequency scaling curves are in very good agreement with the experimentally measured ones. Some discrepancies in the  $V_a$ range of oscillation may be attributed to the homogeneity assumption such that the nucleation temperature of the M1 phase in the homogeneous R phase is lower than that in the realistic inhomogeneous  $VO_2$  samples. The lower the M1 nucleation temperature is, the lower the upper voltage limit for oscillation, because for bias voltages higher than the upper voltage limit the temperature will stay high so that the M1 phase cannot nucleate and the voltage oscillation ceases. Therefore, the upper voltage limit for oscillation calculated for the homogeneous  $VO_2$  is lower than that measured for the generally inhomogeneous sample. The homogeneity assumption is not expected to significantly affect other observed quantities, because we already used in the simulations the experimentally measured resistances, free carrier lifetime, etc.. Figure 3(c) presents the calculated full frequency scaling with  $V_a$  at various  $R_s$ , whose slope decreases with increasing  $R_s$ .

#### IV. ANALYTICAL FORMULAE AND FUNDAMENTAL LIMIT FOR OSCILLATION FREQUENCY

To better understand and engineer the Mott electronic oscillators, we derive approximate analytical expressions for the angular frequency  $\omega$  and range of oscillation by linearizing Eqs. (1-5) around the superheating state [35],

$$\omega^2 \approx \frac{\alpha V_a^2 Q(Q+1)}{4G_{th} CR_s^2}, \ Q = \sqrt{1 - \frac{4G_{th} \Delta TR_s}{V_a^2}}, \quad (6)$$

$$v(R_s) < V_a < 1.71 \sqrt{\alpha G_{th}C} \Delta T R_s - 0.121 \sqrt{\frac{G_{th}}{\alpha C}}, \quad (7)$$

$$R_s > \frac{1.51}{\alpha C \Delta T},\tag{8}$$

with  $v(R_s)$  being a branched function of  $R_s$ ,

$$v(R_s) \approx \begin{cases} 2\sqrt{G_{th}\Delta TR_s}, & R_s < \frac{4}{\alpha C\Delta T}, \\ \sqrt{\frac{\alpha CG_{th}}{2}}\Delta TR_s + \sqrt{\frac{G_{th}}{2\alpha C}}, & R_s > \frac{4}{\alpha C\Delta T}. \end{cases}$$

Here  $\alpha = \beta k_B / \gamma \tau$  is a parameter dependent only on intrinsic properties of VO<sub>2</sub>, where  $\beta$  is a dimensionless



FIG. 4. Comparison of the experimentally measured frequency scaling (crosses) and the analytical frequency formulae derived from this model (solid lines) and the quasi-steady model (dashed lines). The upper panel is for the scaling with  $V_a$  at  $R_s = 4.7$  k $\Omega$  and the lower panel is for the scaling with  $R_s$  at  $V_a = 15$  V.

material-specific constant.  $\Delta T = T_{sh} - T_s$  where  $T_{sh}$  is the superheating temperature.  $G_{th} = L_x L_y h$  is the effective thermal conductance of the device.

Figure 3(b,c) shows the oscillation behaviors predicted by the analytical formulae Eqs. (6-8), which match well with the experimental and simulation results. For fixed  $V_a$ ,  $R_s$ , and C, the frequency increases as the ambient temperature  $T_s$  increases, in agreement with experimental measurements [12]. The calculated  $R_s$  range of oscillation is narrower than the measured one, similar to the case of  $V_a$  range of oscillation for the same reason. We further use the analytical formulae to generate the frequency map over the bias voltage and series resistance and plot it together with the numerically simulated ranges of voltage oscillation [Fig. 3(d)]. The region of oscillation has a shape of a sector, in excellent agreement with the experiment [10]. It terminates at around  $R_s = 1 \ k\Omega$  yet extends to infinite  $R_s$ .

To understand the important role of the nonequilibrium dynamics of free charge carriers in the voltage oscillation, we compare the frequency scaling from the experimental measurements, our nonequilibrium model, and the quasi-steady model [24, 35] in Fig. 4. The frequency scaling from the quasi-steady model is qualitatively different from the experimentally measured ones yet with large quantitative deviations. In contrast, both the magnitudes of the frequencies and the dependence of the frequency on the bias voltage and series resistance obtained from our nonequilibrium model show remarkably good agreement with our experimental results, demonstrating the critical role of the nonequilibrium charge carrier dynamics in the voltage oscillation. The nonequilibrium carrier dynamics also imposes a fundamental limit to the maximal frequency achievable in a VO<sub>2</sub> oscillator. This is contrary to the previous understanding that the oscillation frequency will go arbitrarily high as the RC time constant and the heat-dissipation time constant approach zero. Indeed, the slow internal carrier dynamics will dominate the oscillation process when the external charging/discharging and heating/cooling dynamics become sufficiently fast. Using Eqs. (6-8), we can project the maximal frequency limit of a VO<sub>2</sub> oscillator [35],

$$\nu_M \approx 0.193 \alpha T_{sh} = 7 \text{ MHz.}$$
 (9)

 $\nu_M$  is a fundamental limit to the frequency, i.e., it only depends on the intrinsic parameters of the material. To approach the maximal frequency limit, one needs to lower the ambient temperature, increase the series resistance, and then tune up the voltage to the high bias limit of oscillation. The ability to shift the resonance frequency dynamically makes VO<sub>2</sub> attractive for forming oscillator arrays [22]. Equation (9) also provides guidance on searching for new IMT materials that could form electronic oscillators with gigahertz oscillation frequencies, that is, materials with short carrier lifetimes and small energy gaps in their insulating phases.

#### V. CONCLUSIONS

We presented a nonequilibrium model to predict and understand the dynamics of oscillating IMTs in Mott insulators and experimentally validated it by measuring the voltage oscillation in a two-terminal  $VO_2$  oscillator. The nonequilibrium dynamics of free charge carriers is critical for generating the experimentally observed oscillation behavior, unambiguously demonstrating that the phase transition during the voltage oscillation is partially electronically driven. Such nonequilibrium carrier dynamics may be the missing dynamics in understanding the chaotic voltage oscillation observed in another Mott insulator  $NbO_2$  [39]. We also derived approximate expressions for the oscillation frequency scaling and range of oscillation, revealing that the nonequilibrium carrier dynamics imposes a fundamental limit to the maximal frequency. Subsequently the material property parameters that can enhance the fundamental frequency limit are clearly identified. This physics-based model offers a foundation for future studies of the dynamics of oscillating IMTs and provides guidance on designing highfrequency electronic oscillator devices based on IMT materials.

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